

PROJECTION OPTICAL SYSTEM FOR MASKLESS LITHOGRAPHY

ABSTRACT OF THE DISCLOSURE

A maskless lithography system including an illuminating system, a SLM having a non-linear shape (e.g., curved, concave, spherical, etc.), an exposure system, and a beam splitter that directs light from the illuminating system to the SLM and from the SLM to the exposure system. In some embodiments, an optical element can be located between the beam splitter and the SLM, possibly to correct for aberrations.

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